DUAL VIEW ICP-OES
MINUS THE WAIT

The Measure of Confidence

Agilent 5100 ICP-OES

The fastest ICP-OES... ever.

The Agilent 5100 Synchronous Vertical Dual View (SVDV) ICP-OES revolutionizes ICP-OES analysis. With its unique Dichroic Spectral Combiner (DSC) technology, you can now run axial and radial view analysis at the same time.

Save time and money

- Run the fastest ICP-OES analysis, using less gas.
- Measure all wavelengths in one measurement, for higher precision without delays.
- Start work sooner with the zero gas consumption VistaChip II detector that shortens warm-up time.

Uncompromised performance

- Measure your toughest samples with a vertical torch.
- Achieve long term analytical stability with a solid-state RF system.

Simplify your analysis

- Take the guess work out of method development with intuitive ICP Expert software and DSC technology.
- Powerful software algorithms simplify method development, improve accuracy, and extend your measurement range.

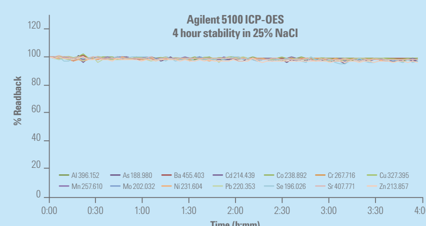
Flexible configurations

The Agilent 5100 is available in three configurations:

- Synchronous Vertical Dual View.
- Vertical Dual View.
- Radial View.

ROBUST AND STABLE

With a vertical torch and robust solid state RF in every configuration, the 5100 ICP-OES handles your toughest samples with ease.

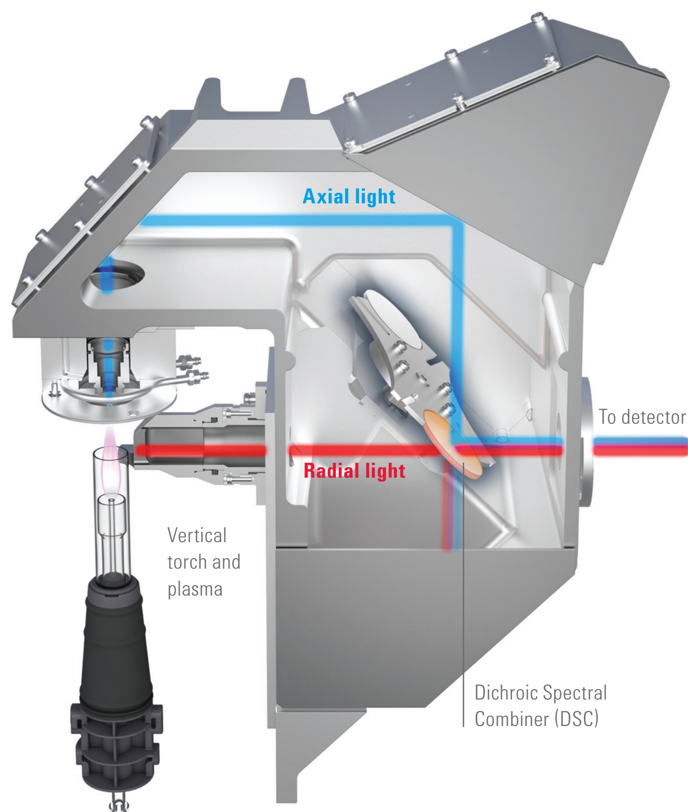


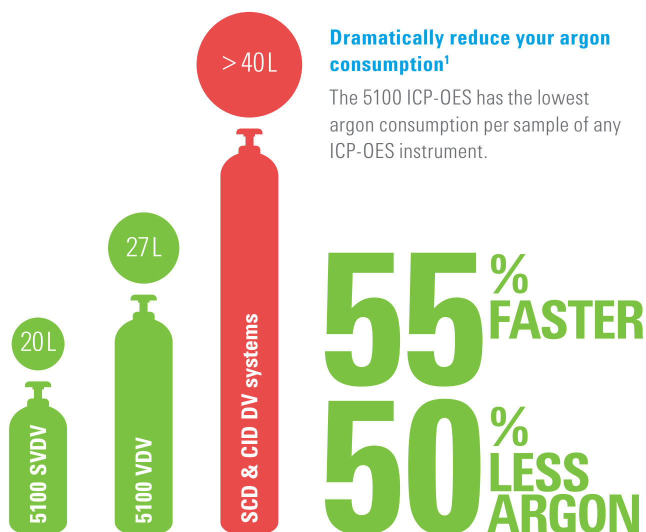
Shown is the percentage readback on a range of elements in a 25% NaCl solution. Readback stability for all elements over 4 hours was < 1.3% RSD, without internal standardization.

Agilent Technologies

How does Synchronous Vertical Dual View work?

The 5100 SVDV ICP-OES needs only a single measurement per sample. The Dichroic Spectral Combiner allows both the axial and radial views of the plasma to be captured in one reading. This delivers accurate results in the quickest possible time[1].





Dramatically reduce your argon consumption[1]

The 5100 ICP-OES has the lowest argon consumption per sample of any ICP-OES instrument.

55% FASTER

50% LESS ARGON

DID YOU KNOW?

Conventional dual view ICP-OES systems require you to set up a series of sequential measurements by selecting which elements are measured in axial mode and which are measured in radial mode.

Some systems also use two slits to measure low and high wavelengths in each mode, resulting in up to four sequential measurements on each sample, making sample throughput slow.

1. The analysis speed and gas consumption figures are compared to competitive systems, based on published application data. Refer to Agilent application note 5991-4821EN

For more information:
Contact your local Agilent representative or visit:
www.agilent.com/chem/5100icpoes

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